

<b>Notice of References Cited</b>	Application/Control No. 10/502,232	Applicant(s)/Patent Under Reexamination EAL H. LEE	
	Examiner Chandra Chaudhari	Art Unit 2891	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,245,207	09-1993	Mikoshiba et al.	257/392
*	B	US-6,156,647	12-2000	Hogan, Barry	438/653
*	C	US-6,204,171	03-2001	Hu, Yongjun	257/E21.584
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf, "Silicon Processing for the VLSI Era", vol. 2, pages 189-193.
	V	Sakamoto, "Preparation and microstructure of reactively sputtered Ti(1-x)Zr(x)N films", Thin Solid Films 228(1993), pages 169-172.
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.